



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

re Application of

Jason M. Benz

Serial No.: 09/695,028

Group Art Unit: 1765

Filed: October 24, 2000

Examiner: Alanko, Anita K.

For: METHOD FOR THIN FILM LASER REFLECTANCE CORRELATION FOR
SUBSTRATE ETCH ENDPOINT

Honorable Commissioner of Patents
Washington, D.C. 20231

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TC 1700
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PRELIMINARY AMENDMENT

Sir:

Prior to examination on the merits and calculation of the filing fee and concurrently with the Request for Continued Examination (RCE) filed herewith, please amend the above-identified application as follows:

IN THE CLAIMS:

Please add the following new claims.

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- 1 -- 34. The method according to claim 1, wherein said etch relation comprises a correlation
2 between the substrate etch rate and the reflectance signal. –

- C1
2 35. The method according to claim 12, wherein said etch ratio comprises a correlation between
the second material etch rate and the reflectance signal.

- 1 36. The method according to claim 23, wherein said etch ratio comprises a correlation between
2 the second material etch rate and the reflectance signal. –
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